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Docket No. 56775 (70551)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

APPLICANT: N. Kanetsuki, et al. EXAMINER: L. Vinh  
U.S.S.N.: 10/015,446 ART UNIT: 1765  
FILED: 12/12/2001  
FOR: Plasma Processing Method

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only*

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**CERTIFICATE OF MAILING**

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on 5/18/04

By: *Eileen Woodbury*

Eileen Woodbury

\*\*\*\*\*  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

**RESPONSE TO FINAL OFFICE ACTION**

The following is in response to the Office Action mailed February 24, 2004, in the above referenced application.

**Amendments to the Claims** are reflected in the listing of claims, which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.

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